

U.S. Department of Commerce, Patent and Trademark				Atty. Docket No.		Application No.		
INFORMATION DISCLOSURE STATEMENT BY APPLICANT				VONA.004US0		09/944,050		
				Applicant(s)		Conf. No.		
(Use several sheets if necessary)				Dannenberg		8351		
				Filing Date		Group		
				August 30, 2001		2872		
U.S. Patent Documents								
*Examiner Initial		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate	
<i>lu</i>	1	6,106,676	8/22/00	Terry et al.				
<i>lu</i>	2	6,514,620	2/4/03	Lingle et al.				
U.S. Published Patent Application Documents								
*Examiner Initial		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate	
Foreign Patent Documents								
							Translation	
		Document	Date	Country	Class	Subclass	Yes	No
OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)								
<i>lu</i>	3	P. A. Greene et al., <i>Modeling of Production Scale Reactive Deposition of a Cylindrical Magnetron</i> , paper associated with an oral presentation made on April 18, 2000 at the 43 rd Annual Technical Conference Proceedings of the Society of Vacuum Coaters of April 15-20, 2000. Pre-prints of the paper were made available by the Society of Vacuum Coaters at the conference proceedings on April 17, 2000.						
<i>lu</i>	4	P. Greene et al., <i>Model of Production Scale Reactive Deposition</i> , paper associated with an oral presentation made at the 42 nd Annual Technical Conference Proceedings of the Society of Vacuum Coaters of April 17-22, 1999. The oral presentation took place during the conference proceedings, although the precise date of the oral presentation is not known. It is believed that pre-prints of the paper were made available by the Society of Vacuum Coaters at some time during the conference proceedings. It is believed that copies of this paper were mailed by the Society of Vacuum Coaters to one or more unknown recipient(s) on a mailing date of August 22, 1999, but not before August 19, 1999.						
<i>lu</i>	5	P. Greene et al., <i>Reactive Deposition and Material Properties of TiO_x, ZnO_x</i> , paper associated with an oral presentation made on June 17, 1999 at conference proceedings of the International Symposium on Sputtering and Plasma Processes (ISSP) in June of 1999. Pre-prints of the paper were made available at some time during the conference proceedings.						
<i>lu</i>	6	R. Dannenberg et al., <i>Reactive Sputter Deposition of Titanium Dioxide</i> , Thin Solid Films 360 (2000) 122-127, published on February 1, 2000.						
Examiner			Date Considered					
<i>[Signature]</i>			September 16 / 2004					
*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with your communication to applicant.								